

[54] NOVEL RESIST SPINNING HEAD

[56] References Cited

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[57] ABSTRACT

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A resist spinning head for preventing photoresist, or electron and X-ray resist from flowing to the edge of the wafer when spin coating in a photoresist spinner, which includes the use of a tapered top plate having a knife-edge contact to the surface of the wafer so as to seal the top of the wafer at an outer ring and prevent resist from flowing under the top plate; whereby the resist is guided, during spinning, by the tapered top surface to the edge of the plate and off the head. The tapered top plate is pressed against the wafer and secured by a spring biasing means to a spinner motor shaft.

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12 Claims, 6 Drawing Figures

